

Packaging Material Characterization and Modeling

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Binghamton, New York?



NGHAMTON NIVERSITY Composite Nature and Warpage

- In most packaging architectures, manufacturing steps occur at elevated temperatures when the assembly is nearly plat. As cooling takes place, out-of plane deformation can occur due to CTE mismatches.
 - Non-uniform expansion/contraction of die and substrate in temperature cycle.
 - Results in warpage of the package which is major reliability concern.





Warpage of Advanced Packages/Assemblies a Prime Driver of *BGA Failure*



Typical FC-CSP

Die Shadow Effect Largest DNP BGA



FOWLP / MUF Packages

Die Shadow Effect Largest DNP BGA



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MSL3

Warpage Driven MUF Delamination



Laminate Strip



Magnification: X200



Singulated MUF Package



Warpage of the Strip in Reflow Temp





Warpage

- Moore's Law: the number of transistors in a dense integrated circuit doubles approximately every two years.
- Advanced Solution: The integration level becomes higher and higher. More and more layers are stacked on each other.



BINGHAMTON UNIVERSITY Warpage Measurement of 15x15 PoP







Top side of bottom Package

Bottom Side of Top Package



Warpage Driven Yield Loss Wettable Gap Measurement



80µm







85μm not pop



More Complicated Warpage

- As the integrated circuit packaging density increasing, 2.5D packaging and 3D packaging were developed.
- More and more layers are stacked on each other, the CTE mismatches between each layers is becoming more critical.





AMD Fiji Package



Package Substrate



Cross Section of GPU Die



Major Technology Challenges

ASIC

- Large die size
- Fine pitch (~40 um)
- High bump count (> 200k)

High Bandwidth Memory (HBM)

- High bump density (~5k)
- Small UBM (25um)
- Inspection thru stacked dies (4 DRAM + 1 Logic inside)



(Source: Hynix)

Interposer

- Huge die size
- Double side handling
- High pad count
- High C4 count (> 20k)
- Warpage control

Package
 Package warpage control



Wafer Warpage

• In chip to wafer or wafer to wafer bonding, the warpage of wafer may lead to serious damage of the devices during thermal compression boning process.





Wafer Warpage During Reflow

• After solidifying the 3D DIC speckle-free method, a 12 inches fully circuited and back-ground wafer is measured from 25°C to 240°C to demonstrate the method effectiveness.





Warpage During Assembly Process

Due to the more and more sophisticated structures, warpage has been a main concern during assembly process. It is one of the root causes of failures in manufacturing processes causing open interconnect.



Assembly flow of TSV interposer package

- The package undergoes reflow process three times. It might lead to the product failure before the final step.
- An in-situ warpage measurement method to monitor the package warpage during assembly process is necessary.



Beyond Traditional Modeling -Assembly Process Modeling

Sim. Vs. Exp. for sample I (substrate+interposer)



BINGHAMTON UNIVERSITY Strip Substrate Warpage Measurement

- Strip substrate is quite thin and light. So it can be warped easily before assembly process. Once it warped, the individual substrate will be affected due to the whole strip warpage.
- It is thin and sensitive, conventional DIC surface treatment will contaminate the specimen and reveal the actual warpage distribution.



Speckle-free 3-D DIC test on a strip substrate



Case 1

μ-bump underfill's isothermal shrinkage and Reliability Impact



Underfill Material Behavior Under Thermal Aging

Underfill Fracture Toughness Kic degradation

K1c	100C	115C	125C	150C	170C
Ohrs	2.2	2.2	2.2	2.2	2.2
500hrs	2.1	2.0	1.8	1.7	1.5
1000hrs	2.0	2.0	1.5	1.4	1.2
1500hrs	2.0	2.0	1.5	1.2	1.0

(unit: MPa*m^0.5)

Underfill shrinkage

Shrinkage%	100C	115C	125C	150C	170C
Ohrs	0	0	0	0	0
500hrs	1%	1%	1%	2%	3%
1000hrs	2%	1%	2%	11%	15%
1500hrs	2%	1%	2%	19%	26%





Underfill Material Behavior Fracture toughness temperature dependence

- Fracture toughness is dependent on the in-situ temperature, as seen in the graph, K_{IC} of the μ -bump underfill is decreasing as the temperature gets higher.
- > χ_{UF} is to identify the degree of G_{IC} decrease when temperature is elevated from 25°C to 150°C.



$$G_{IC} = \frac{K_{IC}^{2}}{E}$$

$$\chi_{UF(150^{\circ}C)} = \frac{G_{IC} (@150^{\circ}C)}{G_{IC} (@25^{\circ}C)} = \frac{6.774 J/m^{2}}{556.7434 J/m^{2}}$$

$$= 0.012168$$



Case1: global & local model

- Use symmetric model; dimensions follow actual part size.
- Meshed with all quadrilateral 8-node Plane183 element under plane strain condition.
- Assume under isothermal, the deformation is only caused by shrinkage of the μ -bump underfill between the die and interposer.
- Ideal crack (two crack surfaces have identical location) for all sub model cases.
- Converged solution could be obtained in the global model until 20% shrinkage.



Failure Mode: Interfacial Crack Propagation

• Case 1:

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- EMC/UF interfacial crack;
- Crack length: 10um; crack tip mesh size: 0.0625um
- Shearing mode (Mode II) crack dominant
- J integral and virtual crack closure (VCCT) method results are consistent in calculating strain energy release rate (ERR).
- Polynomial fitting is done for ERR-shrinkage curve, estimate the ERR as shrinkage increases.







Failure Mode: Interfacial Crack Propagation

- Assume the interfacial critical toughness is the same with the cohesive value.
- Estimated 11% 18% amount of "threshold shrinkage" could drive the crack into further propagation.
- Crack propagation would occur once the threshold shrinkage was reached.





Failure Mode: Cohesive Crack Propagation

- Cohesive crack in underfill
- After delamination of the EMC/underfill interface, a crack tip extends into the underfill.
- Assumed Initial Crack length: 10 um;
- Opening mode (Mode I) dominant.



Equivalent stress (unit: MPa) 1% shrinkage @150 °C



Case 2 *i*MEMS[®] Package Modeling



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CERPAK



Leadless Chip Carrier (5x5x2mm)

Wafer Scale Package (2x2x1mm)



CBGA (7x7x3mm)





Lead frame chip scale package (LFCSP) (4x4x1.45mm)

Capped Die



This is a Major MEMS Industry Breakthrough – Finally removes the concern of single mass 3-axis sensing

ADXL330 enables Nintendo's Gaming Revolution Wij



WI SPORTS



and many more applications...







Package study objects: 4 x 4 x 1.45 mm LFCSP



(b)

4 x 4 x 1.45 mm LFCSP (ADXL330 package)



MEMS Packaging

Why model the stress and device interactions?



Modeling interactions is extremely hard. We take a novel approach:
 Finite element package model + Sensor reduced-order model (CoventorWare) ->

Integrate the two!



LFCSP Package Warpage Measurement



(a) Warpage of the package bottom side (e-pad side) at 20°C.

(b) Warpage plot over -55 ~ 200°C along a diagonal axis.



MEMS Packaging Analysis





Tg and CTE w.r.t Moisture





Process Modeling of MEMS (Package Level)



CHS = 0.44 %strain/%wt $\epsilon_{SW} = 0.44 \times 0.171\% wt_{@60\%RH}$ = 0.075%strain Subjected to 1. Curing shrinkage (175°C, 0.24% shrinkage)

2. Cooling down (25°C/50%RH)

- 3. MSL 3 Preconditioning
- 4. Reflow (30°C~260°C)

5. HAST





FE Model of MEMS (Package Level)

1. 0.24% Curing shrinkage (At 175°C)









Max. UY 4.144 μ m

Max von mises: 48 MPa



FE Model of MEMS (Package Level)

ΛN

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2. Cooling down from 175°C to 25°C and fully saturated at 50% RH



BINGHAMTON UNIVERSITY Moisture Concentration Distribution MSL 3





CASE 3 High Speed DIC Drop Test and Modeling



Experimental Set up







TDM Deformation with Drop height change

- TDM makes first contact with surface at 1.75 msec.
- With increase in drop height the maximum deformation of the center point increases.





Animation for 60 cm TDM Drop

- Video highlights the Deformation of TDM after 60 cm drop.
- Section line runs in horizontal direction passing though center of the module.





CASE 4 2.5D Package Modeling



Influence of lid on thermal performance

- Lid is removed from the lidded package
- Heat sink is directly attached on the silicon dies through TIM2





Influence of lid on thermal

performance





- Removing the lid can effectively reduce the junction and HBM temperature;
- Temperature drop on HBM is less than ASIC;
- R_{ia} decreases by ~ 0.05°C/W.

BINGHAMTON Thermo-mechanical challenges in lidless package

Lidless 2.5D package





- Advantage:
 - better heat dissipation
- Disadvantage:
 - larger warpage
 - moisture penetration
 - risk under mechanical loading

Lidded 2.5D package



- less warpage
- moisture barrier
- less risk under mechanical loading
- Disadvantage:
 - worse heat dissipation

BINGHAMTON Thermo-mechanical reliability assessment

Objective: To investigate the design factors that contribute to the thermal deformation and stress development of the 2.5D package, and to provide design guidelines for building thermo-mechanically reliable 2.5D packages.





Lidless 2.5D package

- Package level reliability
 - warpage and stress
- Board level reliability
 - BGA solder joint reliability under thermal cycling
 - BGA solder joint reliability under power cycling



Parametric study on package level model

Material and geometric parameters are considered in parametric study using 3D finite element analysis

Material Parameter	Value
Substrate Core CTE	6, 8, 10 ppm/°C
Substrate Core modulus	25, 30, 35 GPa
C4 underfill modulus	6.8, 10.8, 14.8 GPa
C4 underfill CTE	20, 27, 34 ppm/ºC
Microbump underfill modulus	5, 8.5, 12 GPa
Microbump underfill CTE	20, 28, 36 ppm/°C
Stiffener CTE	15.5, 17, 18.5 ppm/°C
Adhesive modulus	0.008-3 GPa

Geometric Parameter	Value
Stiffener thickness	1, 1.5, 2mm
Stiffener foot width	4, 6, 8mm
Adhesive thickness	0.1, 0.185, 0.27mm
Adhesive coverage	67%, 83.5%, 100%
Interposer thickness	0.08, 0.11, 0.14mm

Reference temperature-170°C



Two metrics for comparison:

- Substrate warpage in diagonal at 25°C
- Maximum Von-Mises stress in die at 25°C

die stress



Adhesive modulus on substrate warpage and die stress



die stress



Parameter	Trend in warpage	P_warp	Trend in stress	P_stres
Stiffener thickness		0.578		0.737
Stiffener foot width		0.015		0.121
Adhesive thickness		0.272		0.313
Adhesive coverage		0.249		0.524
Interposer thickness		0.994		0.056



Board level study under power cycling

- During real working condition, temperature is non-uniformly distributed, power cycling effect should be considered.
- Thermal analysis
 - 20 min power on, 20 min power off
 - 138W for ASIC and 8 W for each HBM
 - Heat transfer coefficient is applied on heat sink
- Structural analysis
 - Temperature loading
 - Clamping force is applied on heat sink and backing plate
 - Contact condition between backing plate and PCB



Temperature distribution of silicon chips

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Power cycling vs thermal cycling

- Solder reliability is compared between thermal cycling and power cycling condition.
- Solder fatigue life is much higher in power cycling condition





Influence of clamping force

- Different clamping force is considered.
 - 20lb to 180lb
- 100 lb clamping force shows the highest fatigue life





Thank you!

Questions?